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## Amendments to the Claims

The listing of claims below will replace all prior versions and listings of claims in the application. The changes to currently amended claims are shown using strikethrough to identify deleted material and underlining to identify added material.

## Listing of Claims:

- 1-2. (canceled)
- 3. (currently amended) The production process according to claim 1 or 2, A process for producing a compound represented by formula (2):

$$H_3C$$
 $CO_2$ 
 $CO_2$ 
 $CO_2$ 
 $R_2$ 
 $CO_2$ 

that comprises reacting a compound represented by formula (1):

$$H_3C$$
 $OR_1$ 
 $H_3$ 
 $OR_2$ 
 $OR_1$ 
 $H_3$ 
 $OR_2$ 
 $OR_3$ 
 $OR_4$ 
 $OR_3$ 
 $OR_4$ 
 $OR_5$ 
 $OR_5$ 
 $OR_5$ 
 $OR_6$ 
 $OR_7$ 
 $OR$ 

with a thiol compound represented by formula (3):

 $R_3$ -SH (3)

in the presence of a base and optionally eliminating protective group R1:

wherein  $R_1$  is a hydrogen atom, a trimethylsilyl group or a triethylsilyl group; wherein  $R_2$  is an alkyl group having 1 to 10 carbon atoms or a cycloalkyl group having 3 to 10 carbon atoms;

wherein R<sub>3</sub> is-the <u>a</u> thiol residue of a thiol compound represented by formula (4):

$$HS \longrightarrow N \longrightarrow N$$

and wherein R<sub>4</sub> is a hydrogen atom, a trimethylsilyl group or a triethylsilyl group.

4. (currently amended) The production process according to claim 1 or 2, A process for producing a compound represented by formula (2):

$$H_3C$$
 $H_3C$ 
 $S-R_3$ 
 $CO_2$ 
 $O$ 
 $R_2$ 
 $R_2$ 

that comprises reacting a compound represented by formula (1):

with a thiol compound represented by formula (3):

$$R_3$$
-SH (3)

in the presence of a base and optionally eliminating protective group  $R_1$ ;

wherein  $R_1$  is a hydrogen atom, a trimethylsilyl group or a triethylsilyl group;

wherein  $R_2$  is an alkyl group having 1 to 10 carbon atoms or a cycloalkyl group having 3 to 10 carbon atoms;

wherein R<sub>3</sub> is the <u>a</u>thiol residue of a thiol compound represented by formula (5):

and wherein R<sub>4</sub> is a hydrogen atom, a trimethylsilyl group or a triethylsilyl group.

5. (new) The process according to claim 3 or 4, wherein R<sub>2</sub> is a tert-butyl group.